

Title (en)

MIRROR, IN PARTICULAR FOR A MICROLITHOGRAPHIC PROJECTION EXPOSURE APPARATUS

Title (de)

SPIEGEL, INSBESONDERE FÜR EINE MIKROLITHOGRAPHISCHE PROJEKTIONSBELICHTUNGSANLAGE

Title (fr)

MIROIR NOTAMMENT DESTINÉ À UNE INSTALLATION DE LITHOGRAPHIE PAR PROJECTION MICROLITHOGRAPHIQUE

Publication

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Application

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Priority

- DE 102015213253 A 20150715
- EP 2016066178 W 20160707

Abstract (en)

[origin: WO2017009185A1] The invention relates to a mirror, in particular for a microlithographic projection exposure apparatus, wherein the mirror has an optical effective area, having a mirror substrate (205, 305), a reflection layer (220, 320), which is designed such that the mirror has a reflectivity of at least 50% for electromagnetic radiation of a specified operating wavelength, which impinges on the optical effective area (200a, 300a) at an angle of incidence of at least 65° relative to the respective surface normal, and a substrate protection layer (210, 310), which is arranged between the mirror substrate (205, 305) and the reflection layer (220, 320), wherein the substrate protection layer (210, 310) has a transmission of less than 0.1% for EUV radiation.

IPC 8 full level

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Citation (search report)

See references of WO 2017009185A1

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